

AMENDMENTS TO THE CLAIMS:

Please amend the claims as follows:

1. (Currently Amended) A display panel including a first substrate having an array region and an array peripheral region, and a second substrate having a black matrix, the display panel comprising:

a plurality of gate lines on the first substrate;

a gate insulating film on the first substrate including the gate lines;

a plurality of data lines arranged to cross the gate lines, for defining a pixel region on the array region; and

a light leakage prevention film formed between the gate lines and/or data lines of the array peripheral region, for preventing light leakage in areas where said black matrix is not formed, the array peripheral region excluding pixel electrodes.

2. (Previously Presented) The display panel as claimed in claim 1, further comprising:

a TFT and a pixel electrode formed in each pixel region located in the array region.

3. (Original) The LCD panel as claimed in claim 1, wherein the prevention film is formed simultaneously with the gate line to prevent light from leaking.

4. (Original) The LCD panel as claimed in claim 3, wherein the prevention film is formed not to generate a short with the data line.

5. (Original) The LCD panel as claimed in claim 1, wherein the prevention film is formed simultaneously with the data line to prevent light from leaking.

6.-7. (Cancelled).

8. (Original) The display panel as claimed in claim 1, further comprising:
a capacitor metal layer to partially overlap an upper portion of one of the gate lines.

9. (Currently Amended) A method for manufacturing a display panel including a first substrate having an array region and an array peripheral region, and a second substrate having a black matrix, the method comprising the steps of:

forming a plurality of gate lines on the first substrate;
forming a gate insulating film on the first substrate including the gate lines;
forming a plurality of data lines to cross the gate lines and define a pixel region on the array region; and

forming a light leakage prevention film between the gate lines and/or the data lines of the array peripheral region to prevent light leakage in areas where said black matrix is not formed, the array peripheral region excluding pixel electrodes.

10. (Previously Presented) The method according to claim 9, further comprising the steps of:

forming a TFT at a crossing point of a corresponding one of the gate lines and a corresponding one of the data lines;

forming a passivation film on the first substrate including the TFT; and

forming, in the array region, a pixel electrode coupled with the TFT on the passivation film.

11. (Original) The method as claimed in claim 10, further comprising the steps of:

providing the second substrate having the black matrix and a color filter layer; and

forming a liquid crystal layer between the first and second substrates.

12. (Original) The method as claimed in claim 9, wherein the light leakage prevention film is formed simultaneously with at least one of the gate lines to prevent light leakage in the display panel.

13. (Original) The method as claimed in claim 12, wherein the light leakage prevention film is formed of a conductive material having a high reflectivity.

14. (Original) The method as claimed in claim 12, wherein the light leakage prevention film is formed of any one of Cr, Al, Sn, Cu, Mo, Cr/Mo, Cr/Al, or a combination thereof.

15. (Original) The method as claimed in claim 12, wherein the light leakage prevention film is formed to prevent an electrical short with the data lines.

16.-19. (Cancelled).

20. (Original) The method as claimed in claim 9, further comprising the step of:

forming a capacitor metal layer to partially overlap at least one of the gate lines.

21. (Cancelled).